

Notice of References Cited	Application/Control No. 09/218,997	Applicant(s)/Patent Under Reexamination FUKAMI, TERUAKI	
	Examiner Leigh McKane	Art Unit 1744	Page 1 of 1

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*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
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	B	US-5,651,836-A	07-1997	SUZUKI	134/34
	C	US-			
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	I	US-			
	J	US-			
	K	US-			
	L	US-			
	M	US-			

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	N	JP-04083585-A	03-1992	JP	ASAHI CHEM. IND. CO. LTD.	_____
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NON-PATENT DOCUMENTS

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	U	OHMI, T. et al. Abstract of "Metallic impurities segregation at the interface between silicon wafer and liquid during wet cleaning," Journal of the Electrochemical Society, vol. 139 (111), pp.3317-35, 1992.
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*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.